IN THE SPECIFICATION:

Please amend the specification as follows:

On page 5, line 12, please replace the paragraph:

C1

~~FIG. 8~~ FIGS. 8a-8b. Schematic cross-sectional view and top view of a horizontal embodiment of a single-wafer megasonic cleaning apparatus having a pair of transducers mounted on either side of a substrate in accordance with the present invention.

On page 7, line 13, please replace the paragraph:

C2

Two alternate configurations for the apparatus are presented in **FIGS. 2** and **3**. **FIG. 2** shows a schematic cross-sectional elevation view of a first fast single-wafer megasonic cleaning apparatus **200** made in accordance with the present invention. **FIG. 3** shows a schematic cross-sectional elevation view of a second embodiment of a fast single-wafer megasonic cleaning apparatus **200** made in accordance with the present invention. The second embodiment shown in **FIG. 2** uses a smaller footprint to reduce the floor area the tool occupies. In both **FIGS. 2** and **3**, the apparatus **200** includes a container **205** for holding single wafer 90 to be cleaned and for holding the liquid cleaning medium 220, and a megasonic transducer **210** disposed to face the surface of single wafer **90** to be cleaned. Megasonic energy is directed **270** from megasonic transducer **210** toward the surface of single wafer **90** to be cleaned. As described herein below, conventional prior art megasonic transducers, such as those used in the batch ultrasonic cleaning system of FIG 1, are available as an array of megasonic transducers. Such an array of megasonic transducers is more clearly shown in the top view of FIG. 8b as it is applied to the single wafer embodiment of the present invention. As further shown in FIG. 8b, lower array of megasonic transducers 210a' is larger than single wafer 90. From the active surface of each megasonic transducer of the array, megasonic energy is directed at wafer 90, as shown in FIGS. 2, 3, 7, and 8a. However, while individual transducers of the array transmit their energy at various angles, no transducer having an active surface facing perpendicular to the active surface of transducer 210 is provided, as shown in FIGS. 2, 3, 7, 8a, and 8b, and no substantially comparable amount of energy is therefore provided from such a perpendicularly oriented transducer. The apparatus is arranged so that liquid cleaning medium **220** has a free liquid surface **250**, and the liquid flow is shown in **FIGS. 2 and 3** by flowlines **245** within container **205**, by inlet flowlines **240**, and by overflow outlet flowlines **260**, showing that the liquid cleaning medium **220** overflows the container.

On page 10, line 3 to page 11, line 11, please replace the paragraph:

C3

In a horizontal implementation of the invention lower array of transducers **210a'** are held in container **206**, as illustrated in ~~FIG. 8~~ FIGS. 8a, 8b. Lower array of transducers **210a'** have openings **211** between some of the individual transducers of the array for the entrance of fluid **220** into container **206**. Substrate **90** is held above transducers **210a'** with substrate holders **208**. Fluid flows past both sides of substrate **90** before overflowing container **206** at overflows **260**. Upper array of transducers **210b'** can be brought into position with transducer loading arm **212** once substrate **90** has been loaded on holders **208**. This embodiment allows more control over spacing between substrate and transducers than the embodiment of **FIG. 7**. Spacing between the bottom surface of substrate **90** and lower array of transducers **210a'** is fixed by holders **208**. Spacing of top surface from upper array of transducers **210b'** can be controlled by adjusting height of upper array **210b'** to accommodate differences in substrate thickness.